

# DVD Monsoon 2025: Review Quiz-9

Total points 7/10

## Quiz Instruction

- The test will be live from **5:00 PM to 7:00 PM**.
- You must submit your response **before 7:00 PM**; no responses will be accepted afterward.
- Each question may have multiple correct options. You get points only when you select all the correct options and no incorrect option.
- Only **one attempt** is allowed per student.
- You must attempt the quiz using your **college email ID**.

The respondent's email (**abhinav23024@iiitd.ac.in**) was recorded on submission of this form.



✓ **What are the sources of Clock uncertainties?**

1/1

- |   |   |
|---|---|
| <input checked="" type="checkbox"/> Coupling                      | ✓ |
| <input checked="" type="checkbox"/> Temperature                   | ✓ |
| <input checked="" type="checkbox"/> Power Supply Noises           | ✓ |
| <input checked="" type="checkbox"/> IR drop through interconnects | ✓ |
| <input checked="" type="checkbox"/> Through clock generators      | ✓ |

**Feedback**

*Clock uncertainty arises due to variations in the clock's arrival time caused by physical and electrical effects.*

*Temperature changes and power-supply noise alter clock delays.*

*PLL/DLL jitter introduces random edge shifts in the period of the clock signal.*

*Coupling from nearby nets adds additional delay variations, while process variations create mismatched delays across the clock tree.*

*IR drop and delays through interconnects affects the clock signals which makes signal strength weak.*



**✗ Select the incorrect statements out of the given statements**

0/2

- ☐ PnR tools demands that metal layers are placed orthogonally
- ☒ M2 can be placed horizontally or vertically orthogonally with respect to M3. ✗
- ☐ M2 or higher layer bends are not allowed in standard cell area.
- ☒ Higher metal layers have lower capacitances compared to lower metal layers.Hence preffered for local routing of signals ✓
- ☐ Higher metal layers are preffered for power and clock signals because they have less resistance
- ☒ Metal bends cannot have any fabrication effects ✓
- ☒ Metal bends doesnt lead any congestion as higher metal layers are orthogonals ✓
- ☐ Higher metal layers should be placed orthogonally and it will cause no drc issue .
- ☒ metals bends are not related to Vias placements ✓

**Correct answer**

- ☒ Higher metal layers have lower capacitances compared to lower metal layers.Hence preffered for local routing of signals
- ☒ Metal bends cannot have any fabrication effects
- ☒ Metal bends doesnt lead any congestion as higher metal layers are orthogonals
- ☒ metals bends are not related to Vias placements

**Feedback**

*Each metal layer is assigned a preferred routing direction during PnR stage. If all metals are routed in any direction, wires would cross and overlap more often, creating congestion. Hence consecutive metal layers are placed orthogonally*

*Higher metal layers are thicker, have more spacing requirements, and lesser coupling capacitance. So, they also have lower resistance and can be used to route long global signals and clocks.*

*Vias placements can be easier when consecutive metal layers are placed orthogonally, which will results in lesser congestion*



✓ **During Presentation Sir pointed about the sizing of the pmos clock?** 2/2  
**Select the correct statements**

- ☐ Pmos should be sized 0.135um as it will reduces Area in our layout.
- ☐ In Dynamic Circuits, Rise times are not important and they are not part of the evaluation phase
- ☒ It could lead to incomplete charging to VDD before evaluation phase. ✓
- ☐ It will not help in logic Evaluation hence we can keep it small.
- ☒ Noise Margin will get affected. ✓
- ☐ There will be enough time to precharge the circuit.Hence keeping it small and large doesn't matter at all.
- ☒ It can lead to glitch in the output ✓
- ☐ Output will be well settled and do not depends on the sizing of the pmos clock.
- ☒ It can limit the clock frequency at which the circuit is operating. ✓

**Feedback**

*If the pmos is kept small , it will have higher resistance and the charging of the dynamic nodes slows down and the evaluation phase may come before the output is precharged to full VDD.*

*Noise margin will get affected as the node may not get charged to full VDD if the precharge phase is not kept High for too long Thereby reducing Noise margin.*

*Incomplete charging can leads to glitches in the output node.*



✓ **What makes clock skew different from the clock jitter ?Select the correct statements** 2/2

- ☒ clock skew is the difference between the arrival time at the sequential elements ✓
- ☒ Clock jitter is temporal variation and random ✓
- ☒ Clock jitter affects the periodicity of the clock signals. ✓
- ☒ Both affects the performance of the design. ✓

**Feedback**

*Clock skew is systematic, deterministic difference in arrival time of the same clock edge at two different flip flops.*

*clock jitter is random or variation in the timing of a clock edge at a single circuit element*



✗ Which of the following statements are incorrect based on your understanding while making layouts.

0/1

- ☒ There is no problem in splitting nwell as no drc will occur regarding breaking of nwells. ✓
- ☐ We may face NW-NW DRC's and No LVS error will occur
- ☒ There will be LVS error if Nwells are not spaced properly upto minimum drc. ✓
- ☐ We will encounter LVS error if NW's are not connected.
- ☐ There is minimum area related drc with respect to NW.

Correct answer

- ☒ There is no problem in splitting nwell as no drc will occur regarding breaking of nwells.
- ☒ We may face NW-NW DRC's and No LVS error will occur
- ☒ There will be LVS error if Nwells are not spaced properly upto minimum drc.

Feedback

*NWell have minimum area related DRC.*

*Nwell can be split but it should be connected otherwise we will have LVS S\_CONNECT issue.*

*If two NWell are separated and kept separately then it will have some DRC constraints .*



✓ **At what PVT Corners should be simulate our design for sub threshold leakage** \*1/1

- ☐ PMOS - Fast; NMOS - Fast; VDD - 1.08; Temperature - Low
- ☐ PMOS - Slow; NMOS - Slow; VDD - 1.32; Temperature - High
- ☐ PMOS - Fast; NMOS - Fast; VDD - 1.32; Temperature - low
- ☒ PMOS - Fast; NMOS - Fast; VDD - 1.32; Temperature - High ✓

#### Feedback

*Subthreshold Leakages increase exponentially at high temperatures.*

*Sub-threshold current is also higher at high voltages because electrons have high energy and effectively available for charge transfer (current).*

*Fast lots have lower threshold voltage, indicating that higher current is possible at lower voltages. So, sub-threshold leakage is higher.*



✓ During the presentation, we saw that one group placed all the input pins of their design continuously, without spreading them out. What implications could this have?

- ☐ It reduces capacitance and results in fewer DRC violations
- ☐ It makes accessing the pins using higher metal layers easier
- ☒ It could lead to congestion ✓
- ☐ Routing efficiency will increase and pins can be accessed through vias using higher metal layers

#### Feedback

*Pins should be uniformly spread rather placed close to each other. Adjacent placement can cause routing congestion especially due to constraints placed by foundries and/ or PnR tools to route metals in single direction.*

*More congestion also results in increased capacitances at the inputs.*

This form was created inside of IIIT Delhi. - [Contact form owner](#)

Does this form look suspicious? [Report](#)

Google Forms





